AN 121:241716 HCA Full-text
TI Electrophotographic liquid developer
IN Kato, Eiichi
PA Fuji Photo Film Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 63 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06051569	A2	19940225	JP 1992-219554	19920728
	JP 2916560	B2	19990705		
PRAI	JP 1992-219554		19920728		

AB In the title developer containing at least resin particle dispersion in a nonaq. solvent with an elec. resistivity ≥109 Ωcm and a dielec. constant ≤3.5, the resin particles are made of a A-B block graft copolymer grain obtained by the steps of: (1) forming a A block made up of (a) a monofunctional monomer, a macromonomer with Mw≤10,000 having polymerizable double bond only one end of the backbone chain, a polyfunctional monomer, and a polymer component with a polar moiety; (2) forming an A-B block copolymer, in which a B block contains a polymerizable component and a monofunctional polymerizable double bond at the end of the B block, (3) polymerizing a monomer containing C≥8 aliphatic, and (4) further polymerizing the resulting polymer in a dispersion stabilizing resin soluble in the nonaq. solvent.

IC ICM G03G009-13
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST electrophotog liq developer polymer particle
IT Electrophotographic developers
(resin particles in electrophotog. liquid developer)
IT 112955-45-0P 112955-56-3P 114512-15-1P 138005-06-8DP, carboxy-terminated, ester with glycidyl methacrylate 138115-34-1DP, Ethylmethacrylate-triphenylmethyl methacrylate block copolymer, hydrolyzed, carboxylated, ester with 2-hydroxyethyl methacrylate 138232-67-4DP, Benzyl methacrylatebutyl methacrylate block copolymer, hydrolyzed, methylstyrene-terminated 139104-82-8P 139104-86-2P 139104-87-3P 139104-88-4P 139104-90-8P 139104-94-2P 139104-96-4P 139105-01-4P 139105-03-6P 139105-07-0P 139105-08-1P 139105-10-5P 139105-12-7P 139357-83-8DP, hydrolyzed, terminated with Et methacrylate 139598-52-0DP, Acrylic acid-octadecyl methacrylate block copolymer,

hydrolyzed, hydroxy-terminated, ester with 2-isocyanatoethyl methacrylate
139598-53-1P 139598-54-2DP, hydrolyzed 139598-55-3DP, hydrolyzed
139598-56-4DP, hydrolyzed 139598-57-5DP, hydrolyzed 139598-58-6DP,
hydrolyzed 139598-59-7DP, hydrolyzed 139598-60-0DP, hydrolyzed
139598-61-1DP, hydrolyzed 139598-62-2DP, hydrolyzed 139598-63-3DP,
hydrolyzed 139598-64-4DP, hydrolyzed 139598-65-5P 139598-66-6P
139598-68-8P 139598-69-9P 139598-70-2P 139598-71-3P 139598-72-4P
139598-73-5P 139598-74-6P 139598-75-7P 139598-76-8P 139598-77-9P
139598-80-4P 139598-81-5P 139598-82-6P 139598-83-7P 139598-85-9P
139687-39-1P 141349-31-7P 141414-91-7P 141415-33-0P 141415-66-9P
141440-78-0P 141759-32-2P 141759-37-7P 141759-91-3P 143709-75-5P
147045-28-1P **147127-63-7P** 147130-24-3P 147130-26-5P
147130-28-7P 147130-29-8P 147130-30-1P 147130-31-2P 147130-32-3P
147130-33-4P 147130-35-6P 147130-36-7P 147130-37-8P 147130-38-9P
147130-40-3P 147130-41-4P 147130-42-5P 147130-44-7P 147130-45-8P
147130-47-0P 147130-50-5P 150958-16-0DP, hydrolyzed, terminated with
methylstyrene 156202-69-6P 156620-35-8P 156620-37-0P
158008-00-5DP, hydrolyzed 158008-02-7P 158348-52-8P 158463-91-3P
158463-92-4P 158463-93-5P 158463-94-6P 158463-95-7P 158463-96-8P
158463-97-9P 158463-98-0P 158463-99-1P 158464-00-7P 158464-01-8P
158464-02-9P 158464-03-0P 158464-04-1P 158464-05-2P 158464-06-3P
158464-07-4P 158464-08-5P 158464-10-9DP, hydrolyzed 158464-11-0P
158464-12-1P 158464-13-2P 158464-14-3P 158464-15-4P 158464-16-5P
158464-18-7P 158464-19-8DP, hydrolyzed
RL: MOA (Modifier or additive use); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(electrophotog. liquid developer)

IT 158464-09-6
RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(star copolymer initiator; electrophotog. liquid developer)

IT 138005-17-1P

RL: MOA (Modifier or additive use); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(star-branched; electrophotog. liquid developer)

AN 125:202403 HCA Full-text
TI Wax patterns for manufacture of molds to be used in investment casting and
manufacture of precision cast products
IN Nakayama, Shinichi; Nikashiwa, Toshiki
PA Yamanashi Prefecture, Japan; Nippon Catalytic Chem Ind
SO Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08155586	A2	19960618	JP 1994-305087	19941208
PRAI	JP 1994-305087		19941208		

AB The wax patterns are manufactured from vinyl polymers containing 50-100 weight% repeating unit -CH3C(R1)(BR2)- (R1 = H or Me, R2=C15-30 aliphatic hydrocarbon, B=-C(:O)O-, -C(:O)NHCH2CH2OC(:O)-, -C(:O)NHC(OH)CH2OC(:O)-, -C(:O)NHCH2CH2OC(:O)NHR3NHC(:O)O-, R3=divalent organic group) and/or repeating unit C(COOR4)HC(COOR5)H- (R4, R5= independently H or C1-30 aliphatic hydrocarbon, but at least one of R4 and R5=C15-30 aliphatic hydrocarbon). Dewaxing in the manufacture of precision cast products is conducted by solvent washing or heating and solvent washing. The productivity and quality of precision cast products are improved.

IC ICM B22C009-04
ICS B22C009-18; C08F018-10; C08F020-18; C08F020-58; C08F020-60; C08F022-12
CC 56-2 (Nonferrous Metals and Alloys)
ST vinyl polymer wax pattern investment casting
IT Waxes and Waxy substances
RL: TEM (Technical or engineered material use); USES (Uses)
(vinyl polymer-based wax patterns for manufacture of molds to be used in
investment casting and manufacture of precision cast products)
IT Casting process
(investment, vinyl polymer-based wax patterns for manufacture of molds to be
used in investment casting and manufacture of precision cast products)
IT 25639-21-8 25986-77-0 **181123-73-9** 181123-76-2
RL: TEM (Technical or engineered material use); USES (Uses)
(vinyl polymer-based wax patterns for manufacture of molds to be used in
investment casting and manufacture of precision cast products)